

Supporting Information

High quality UV optoelectrical and high mobility T-ODL/Ti:ZnO epilayers on amorphous substrate through tailoring interfacial nucleation process by atomic layer deposition

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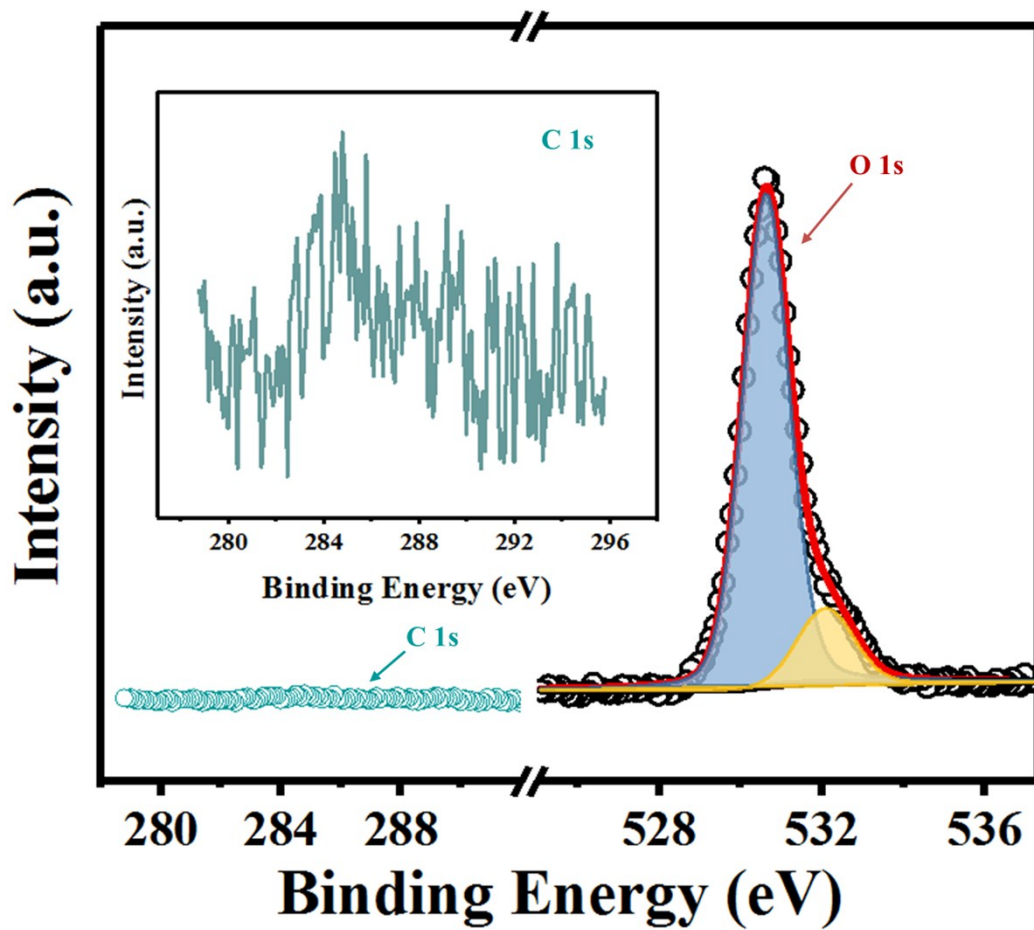


Figure S1. High resolution XPS profiles for C 1s and O 1s core levels of the Ti:ZnO film. Inset is the enlarged view for the C 1s line.

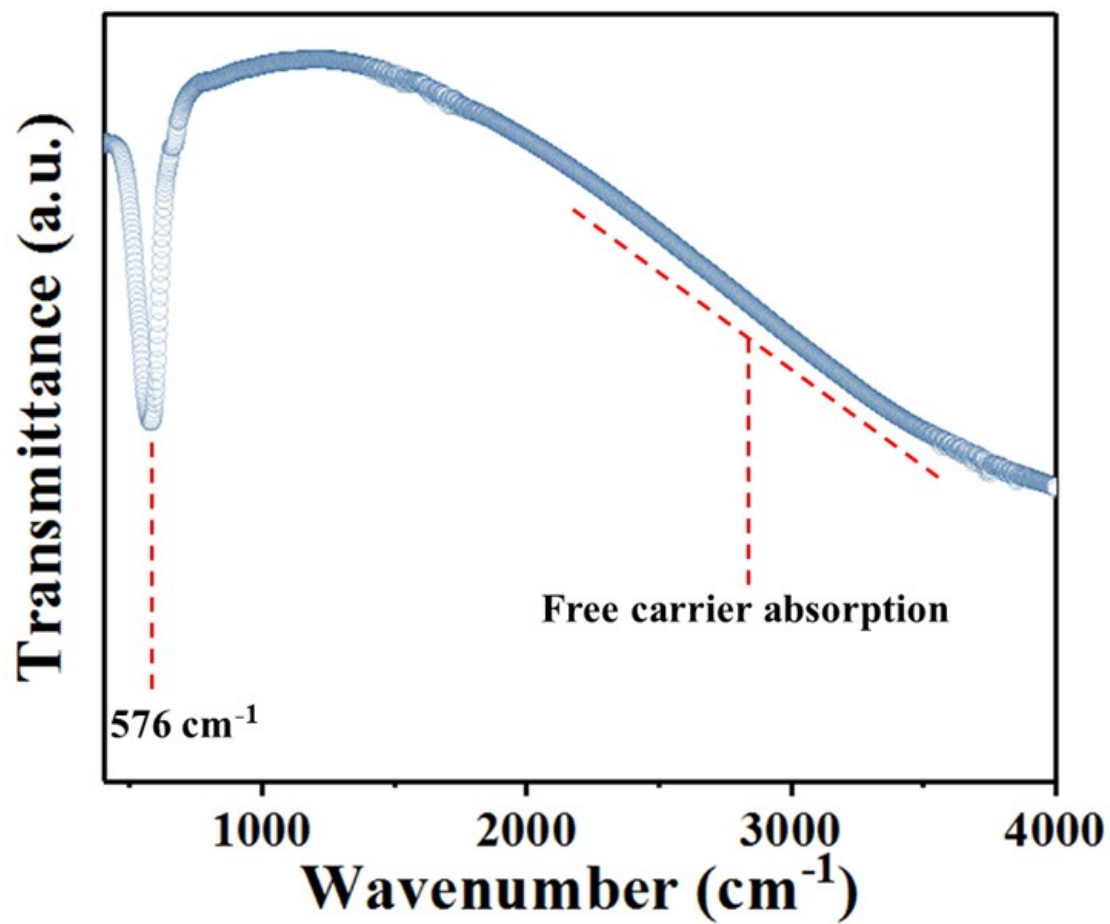


Figure S2. Fourier transform infrared (FTIR) transmittance spectrum of ALD ZnO film.